

Sheet 1 of 1

Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office		Attorney's Docket No. <b>10559-882001</b>	Application No. <b>10/693,373</b>
	Applicant <b>Yan Borodovsky</b>			
	Filing Date <b>October 24, 2003</b>		Group Art Unit <b>1756</b>	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
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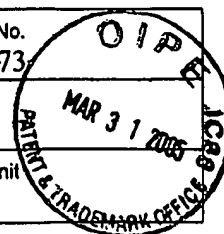
Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (Include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<i>JD</i>	AQ	"Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography"; Fritze et al.; Journal Vacuum. Sci Technology B; Vol. 19, No. 6, pp. 1366-1370; Nov/Dec 2001
	AR	
	AS	
	AT	

Examiner Signature <i>John Richardson</i>	Date Considered <i>09/17/05</i>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Disclosure Form (PTO-1449)

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### U.S. Patent Documents

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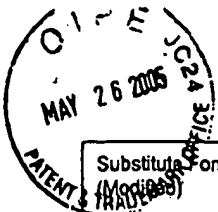
### Foreign Patent Documents or Published Foreign Patent Applications

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	AE							
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### Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
WD	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
WD	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
WD	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
WD	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
WD	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
WD	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1 \approx 0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
WD	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
WD	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
WD	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
WD	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging.", Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

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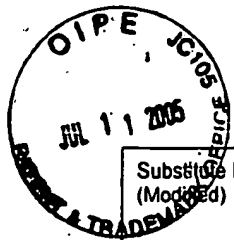
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U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
PD	AA	2005/0073671	04/2005	Borodovsky			
PD	AB	2005/0074698	04/2005	Borodovsky			
PD	AC	2005/0083497	04/2005	Borodovsky			
PD	AD	2005/0085085	04/2005	Borodovsky			
PD	AE	5,759,744	06/1998	Brueck, et al.			
PD	AF	6,042,998	03/2000	Brueck, et al.			
PD	AG	6,233,044	05/2001	Brueck, et al.			
PD	AH	6,548,820	04/2003	Mermelstein			
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U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
<i>PD</i>	AA	5,759,744	June 2, 1998	Brueck, et al.			
<i>PD</i>	AB	5,415,835	May 16, 1995	Brueck, et al.			
<i>PD</i>	AC	5,328,807	July 12, 1994	Tanaka, et al.			
<i>PD</i>	AD	6,553,562	April 22, 2003	Capodieci, et al.			
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<i>PD</i>	AL	EP 0855623	July 29, 1998	EP				
<i>PD</i>	AM	WO 98/32054	July 23, 1998	PCT				
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	AP							

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<i>PD</i>	AQ	Ishibashi, et al., "AFM Lithography Combined with Optical Lithography", <i>IEEE Microprocesses and Nanotechnology Conference 2000</i> , pp. 192-193 (July 2000).
<i>PD</i>	AR	Martin, et al., "Ordered Magnetic Nanostructures: Fabrication and Properties", <i>J. Magnetism and Magnetic Materials</i> , 256(1-3):449-501 (January 2003).
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	<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)		
	Applicant Yan Borodovsky		Group Art Unit 1756
		Filing Date October 24, 2003	

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
ND	AA	2003/0091940	05/2003	Nakao			
ND	AB	5,705,321	01/1998	Brueck, et al.			
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ND	AL	0 915 384	05/1999	Europe				
ND	AM	0 964 305	12/1999	Europe				
ND	AN	WO2005/036273	04/2005	WIPO				
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